

 SCANNED <u>KW</u> O.I.P.E. <u>2</u> Q.A. <u>IN</u>	PATENT DATE
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APPLICATION NO. 09/617454	CONT/PRIOR	CLASS 134	SUBCLASS 001.1	ART UNIT 1746	EXAMINER SHEPHERD MARKOFF MARKOFF
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Method for cleaning plasma etch chamber structures

TITLE

PTO-204
12/93

ISSUING CLASSIFICATION											
ORIGINAL				CROSS REFERENCE(S)							
CLASS		SUBCLASS		CLASS	SUBCLASS (ONE SUBCLASS PER BLOCK)						
INTERNATIONAL CLASSIFICATION											

☐ Continued on Issue Slip inside File Jacket

<input type="checkbox"/> TERMINAL DISCLAIMER	DRAWINGS			CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed. <input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S Patent. No. _____ _____ _____	_____ (Assistant Examiner) (Date)			NOTICE OF ALLOWANCE MAILED _____	
	_____ _____ (Primary Examiner) (Date)			ISSUE FEE Amount Due Date Paid	
ISSUE BATCH NUMBER					
<input type="checkbox"/> The terminal ____ months of this patent have been disclaimed.	_____ (Legal Instruments Examiner) (Date)				

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